

## EUROPEAN PATENT OFFICE

## Patent Abstracts of Japan

PUBLICATION NUMBER : 01249619  
PUBLICATION DATE : 04-10-89

APPLICATION DATE : 30-03-88  
APPLICATION NUMBER : 63074435

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INT.CL. : C01B 33/06

TITLE : PRODUCTION OF METAL SILICIDE TARGET HAVING HIGH MELTING POINT

ABSTRACT : PURPOSE: To simply obtain the subject dense target having high quality, strictly controlled compsn. and ideally dense structure, by heat-treating a sintered compact obtd. by hot-pressing and reacting mixed powder of a metal having high melting point and Si powder, in an inert gas atmosphere.

CONSTITUTION: The mixed powder of the metal powder having high melting point and 1-100 $\mu$  mean particle size (e.g., W) and the Si powder in 2.1-3.0times mol as much as the amt. of the metal powder, is packed in a graphite mold, set in a vacuum hot-press furnace, heated up to 1000°C without pressing after making vacuum to 0.0001Torr, thereafter further heated up to a fixed temp. (1100-1400°C) and hot-pressed and reacted while keeping at the temp. for fixed time (0.15-8.0hr). Then, the obtd. sintered compact is heat-treated in the inert gas atmosphere by hot-pressing, etc.

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